

Amendments to th Abstract are as follows:

A functional multilayer film and a method for manufacturing the same is provided ~~wherein~~ in which the intervals of fine metallic bodies in the thickness direction ~~of film~~ and the arrangement thereof in the surface direction ~~of film~~ are regular, and the fine metallic bodies arranged on each layer ~~in the surface direction of film~~ are aligned in the thickness direction ~~of film~~.

A functional multilayer film is obtained by fixing a plurality of fine metallic bodies 4 to a matrix 1 made of a dielectric substance. The matrix 1 is obtained by laminating metal-arranged thin films, which each ~~metal-arranged thin film comprising~~ contain a dielectric thin film 2 ~~formed to have~~ having a predetermined thickness and the fine metallic bodies 4 arranged on the dielectric thin film. A plurality of recesses 3a is regularly formed on the surface 2 of the dielectric thin film 2, and the fine metallic bodies 4 are arranged in the lower parts of the recesses 3a.